

Supporting Information for

FIB Secondary Etching Method for Fabrication of Fine CNT Forest Metamaterials

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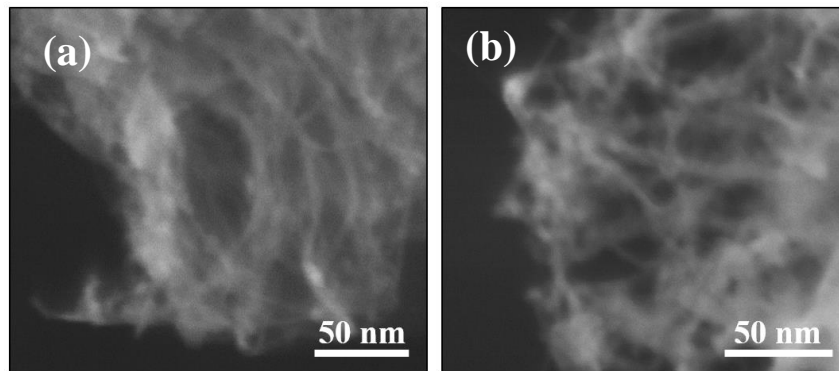


Fig. S1 High resolution SEM images of CNT arrays grown using patterning depth of 10 nm and FIB secondary etching depth of 0.5 nm. Magnification of **a** $\times 400\,000$, and **b** $\times 500\,000$